PTO/SB/08A (10-01)

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Substitute	e for form 1449A/	PTO		Co	mplete if Known
	INFORMATION DISCLOSURE		Application Number	10/627,155	
INFO	RMATIO	N DIS	CLOSURE	Filing Date	7/24/03
STA	TEMENT	RY A	PPLICANT	First Named Inventor	Patel
OIA		<b>.</b>		Art Unit	Not Yet Assigned 7813
(	'use as many si	heets as i	necessary)	Examiner Name	Not Yet Assigned
Sheet	1	of	6	Attomey Docket Number	P102-US

			U.S. PATI	ENT DOCUMENTS	
Examiner initials	T	Document Number Number - Kind Code <sup>2</sup> (if known	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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				Application Number	10/627,155	
INFORMATION DISCLOSURE		Filing Date	7/24/03			
STATEMENT BY APPLICANT			PLICANT	First Named Inventor	Patei	
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Sheet	2	of	6	Attorney Docket Number	P102-US	

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Examiner	Cite	Document Number	Publication Date	Name of Patentee or	Pages, Columns, Lines, Where
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Application Number	10/627,155
Filing Date	7/24/03
First Named Inventor	Patel
Art Unit	Not Yet Asstaned 2813
Examiner Name	Not Yet Assigned
Attorney Docket Number	P102-US

	 	U.S. PATE	ENT DOCUMENTS	
Examiner Initials	Document Number Number - Kind Code * (If known	Publication Date	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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<b>3</b>					l

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Complete if Known Substitute for form 1449B/PTO 10/627.155 **Application Number** INFORMATION DISCLOSURE 7/24/03 Filing Date First Named Inventor Patel STATEMENT BY APPLICANT Not Yet Assigned Group Art Unit Not Yet Assigned **Examiner Name** (use as many sheets as necessary) Attorney Docket Number P102-US of Sheet

	OTHER PRIOR ART NON PATENT LITERATURE DOCUMENTS	
Examiner Cite	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	,
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		OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS	
Examiner Initials	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue oumber(s), publisher, city and/or country where published	Τ2
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		OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS	-
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Attorney Docket No. P102-US

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Patel, et al.

Art Unit: Not Yet Assigned

Serial No.:

10/627,155

Examiner: Not Yet Assigned

Filed: 7/24/03

For:

A MICROMIRROR ARRAY DEVICE WITH SMALL PITCH SIZE

## INFORMATION DISCLOSURE STATEMENT PURSUANT TO 37 CFR 1.97(b)

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-145

Sir:

The attention of the Patent and Trademark Office is hereby directed to the following documents:

serial number 10,627,302 to Patel, et al, filed July 24, 2003; serial number 10,627,303 to Patel, et al, filed July 24, 2003;

The attention of the Patent and Trademark Office is hereby also directed to the documents listed on the attached PTO Form 1449. Copies of the cited references are enclosed.

No fee or certification is required in connection with this Information Disclosure Statement, since it is being submitted prior to the last of (1) issuance of a first official action on the merits and (2) expiration of the three month period following filing of the above-captioned application.

The above information is presented so that the Patent and Trademark Office can determine any materiality thereof to the claimed invention. It is respectfully requested that the information be considered during the prosecution of this application and that the cited documents be listed on the front page of any patent issuing from this application.

6-18-0

INFORMATION DISCLOSURE CITATION  NOV 2 9 2004 FI PTO-1449			ATTY. DOCKET NO. SE		ERIAL NO.				
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			APPLICANT Patel, et al						
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